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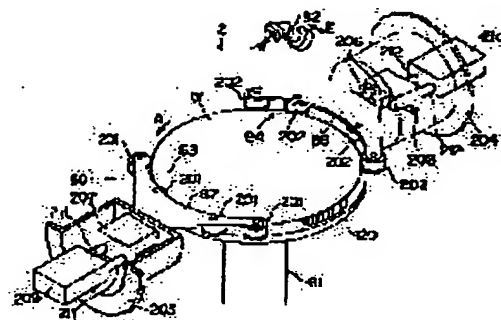
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(54) SUBSTRATE PROCESSING SYSTEM

(57)Abstract:

PURPOSE: To clean a substrate efficiently in a short time by processing the substrate being gripped rotatably at a gripping part having a plurality of rollers abutting against the peripheral edge of the substrate.

CONSTITUTION: A rear surface cleaning system 2 comprises a mechanism 80 for oscillating a wafer W while gripping, a brush cleaning mechanism 81 touching and cleaning the rear surface of the wafer W, and a surface cleaning nozzle 82 for jetting pure water to the rear surface of the wafer W. The wafer gripping mechanism 80 turns the wafer W idly in the direction of an arrow A and the gripping parts 83, 84 thereof comprises rollers 201, 202 disposed along the outer periphery of the wafer W while being spaced apart from each other, and gripping arms 87, 88 for supporting the rollers 201, 202 rotatably. This structure prevents the processing of substrate from being missed at the part where the roller abuts on the substrate thus cleans the substrate effectively in a short time.



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